

Electronic Acknowledgement Receipt

EFS ID:	1036749
Application Number:	10624712
Confirmation Number:	3646
Title of Invention:	TECHNIQUE FOR FORMING CONTACTS FOR BURIED DOPED REGIONS IN A SEMICONDUCTOR DEVICE
First Named Inventor:	Ralf van Bentum
Customer Number:	23720
Filer:	J. Mike Amerson/Mary Paul
Filer Authorized By:	J. Mike Amerson
Attorney Docket Number:	2000.106700
Receipt Date:	02-MAY-2006
Filing Date:	22-JUL-2003
Time Stamp:	17:14:42
Application Type:	Utility
International Application Number:	

Payment information:

Submitted with Payment	no
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File Listing:

Document Number	Document Description	File Name	File Size(Bytes)	Multi Part	Pages
1	Miscellaneous Incoming Letter	Letter_re_issue_fee.pdf	126886	no	1

Warnings:**Information:**

2	Issue Fee Payment Recorded	Fees_Transmittal_PTOL_85.pdf	64648	no	1
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Warnings:**Information:**

Total Files Size (in bytes):	191534
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New Applications Under 35 U.S.C. 111

If a new application is being filed and the application includes the necessary components for a filing date (see 37 CFR 1.53(b)-(d) and MPEP 506), a Filing Receipt (37 CFR 1.54) will be issued in due course and the date shown on this Acknowledgement Receipt will establish the filing date of the application.

National Stage of an International Application under 35 U.S.C. 371

If a timely submission to enter the national stage of an international application is compliant with the conditions of 35 U.S.C. 371 and other applicable requirements a Form PCT/DO/EO/903 indicating acceptance of the application as a national stage submission under 35 U.S.C. 371 will be issued in addition to the Filing Receipt, in due course.